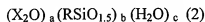
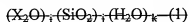


Amendments to the Claims:

1. (Currently Amended) A composition for forming a porous film comprising a condensation product and an organic solvent wherein the condensation product is obtained by adding acid to at least one compound selected from the group consisting of silicate represented by formula (1) and organosilicate represented by formula (2)



wherein X independently represents Li, Na, K, Rb, Cs or quaternary ammonium; i, j and k independently represent numbers which satisfy $0 < i \leq 1$, $0 < j \leq 1$ and $0 \leq k \leq 2$; R independently represents a hydrogen atom or an organic group; and a, b and c independently represent numbers which satisfy $0 < a \leq 1$ and $0 < b \leq 1$ and $0 \leq c \leq 1.5$.

2. (Original) The composition for forming a porous film according to Claim 1 wherein said quaternary ammonium comprises an alkyl group having 1 to 20 carbons.

3. (Original) The composition for forming a porous film according to Claim 1 wherein said R represents an organic group having 1 to 10 carbons.

4. (Currently Amended) The composition for forming a porous film according to Claim 1 wherein said silicate represented by formula (1) is tetramethylammonium silicate and said organosilicate represented by formula (2) is tetramethylammonium methylsilicate.

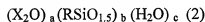
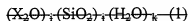
5. (Previously Presented) A method for manufacturing a porous film comprising steps of applying a composition according to Claim 1 to a substrate so as to form a film thereon, drying the film and heating the dried film so as to harden the film.

6-12. (Cancelled)

13. (Previously Presented) The composition for forming a porous film according to Claim 1, wherein the composition is capable of forming a porous film having a modulus of elasticity of 5 to 50 GPa.

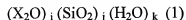
14. (Previously Presented) The composition for forming a porous film according to Claim 1, wherein the composition is capable of forming a porous film having a dielectric constant of 2.3 or less.

15. (Currently Amended) A composition for forming a porous film comprising a condensation product and an organic solvent wherein the condensation product is obtained by adding acid to at least one compound selected from the group consisting of silicate represented by formula (1) and organosilicate represented by formula (2)



wherein X independently represents Li, Na, K, Rb, Cs or quaternary ammonium; i, j and k independently represent numbers which satisfy $0 < i \leq 1$, $0 \leq j \leq 1$ and $0 \leq k \leq 2$; R independently represents a hydrogen atom or an organic group; and a, b and c independently represent numbers which satisfy $0 < a \leq 1$ and $0 < b \leq 1$ and $0 \leq c \leq 1.5$, and wherein the condensation product and the organic solvent are in the form of a coating liquid that is capable of being applied as a film with a spin coater.

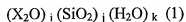
16. (New) The composition for forming a porous film according to Claim 1 wherein said condensation product is obtained by adding acid to said organosilicate and at least one silicate represented by formula (1)



wherein X independently represents Li, Na, K, Rb, Cs or quaternary ammonium and i, j and k independently represent numbers which satisfy $0 < i \leq 1$, $0 < j \leq 1$ and $0 \leq k \leq 2$.

17. (New) The composition for forming a porous film according to Claim 16, wherein said silicate is tetramethylammonium silicate.

18. (New) The composition for forming a porous film according to Claim 15 wherein said condensation product is obtained by adding acid to said organosilicate and at least one silicate represented by formula (1)



wherein X independently represents Li, Na, K, Rb, Cs or quaternary ammonium and i, j and k independently represent numbers which satisfy $0 < i \leq 1$, $0 < j \leq 1$ and $0 \leq k \leq 2$.

19. (New) The composition for forming a porous film according to Claim 18, wherein said silicate is tetramethylammonium silicate.